

# TEM and SEM-CL studies of $\beta$ -SiC nanowires

F. Rossi, F. Fabbri, G. Attolini, M. Bosi, B.E. Watts, G. Salviati  
 IMEM-CNR Institute, viale Usberti 37/A, 43100 Parma (Italy)

## INTRODUCTION

The combination of the distinctive physical and chemical properties of SiC and unique advantages of nanowires (NWs) opens promising near-future perspectives for the design and fabrication of nano-scale devices. The main interests are addressed to nano-electronic devices (e.g. nano field-effect transistors) and nano-electromechanical systems able to operate even in harsh environments, and to nano-sensors exploiting the SiC NWs as biocompatible nanoprobe for biological systems.

## GROWTH PROCESS

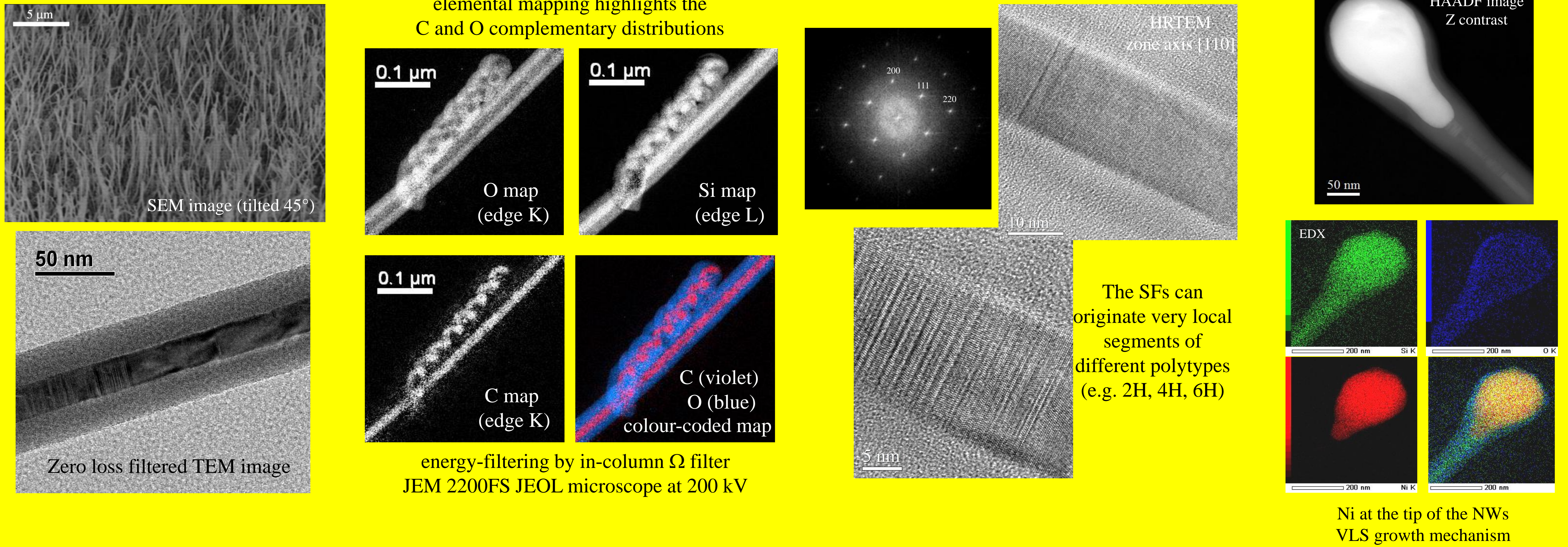
A) core/shell  $\beta$ -SiC/SiO<sub>2</sub> NWs are grown by a CVD process on n-type Si (001) substrates, using carbon monoxide as the carbon source and nickel nitrate as the catalyst.

$\beta$ -SiC (without shell) NWs are obtained with two different methods:  
 B) using VPE technique in a home-made reactor with propane and silane precursor and Ni as catalyst, on Si (100) and (111) substrates.

C) by a chemical reaction using carbon tetrachloride (CCl<sub>4</sub>) as a precursor and Ni as catalyst.

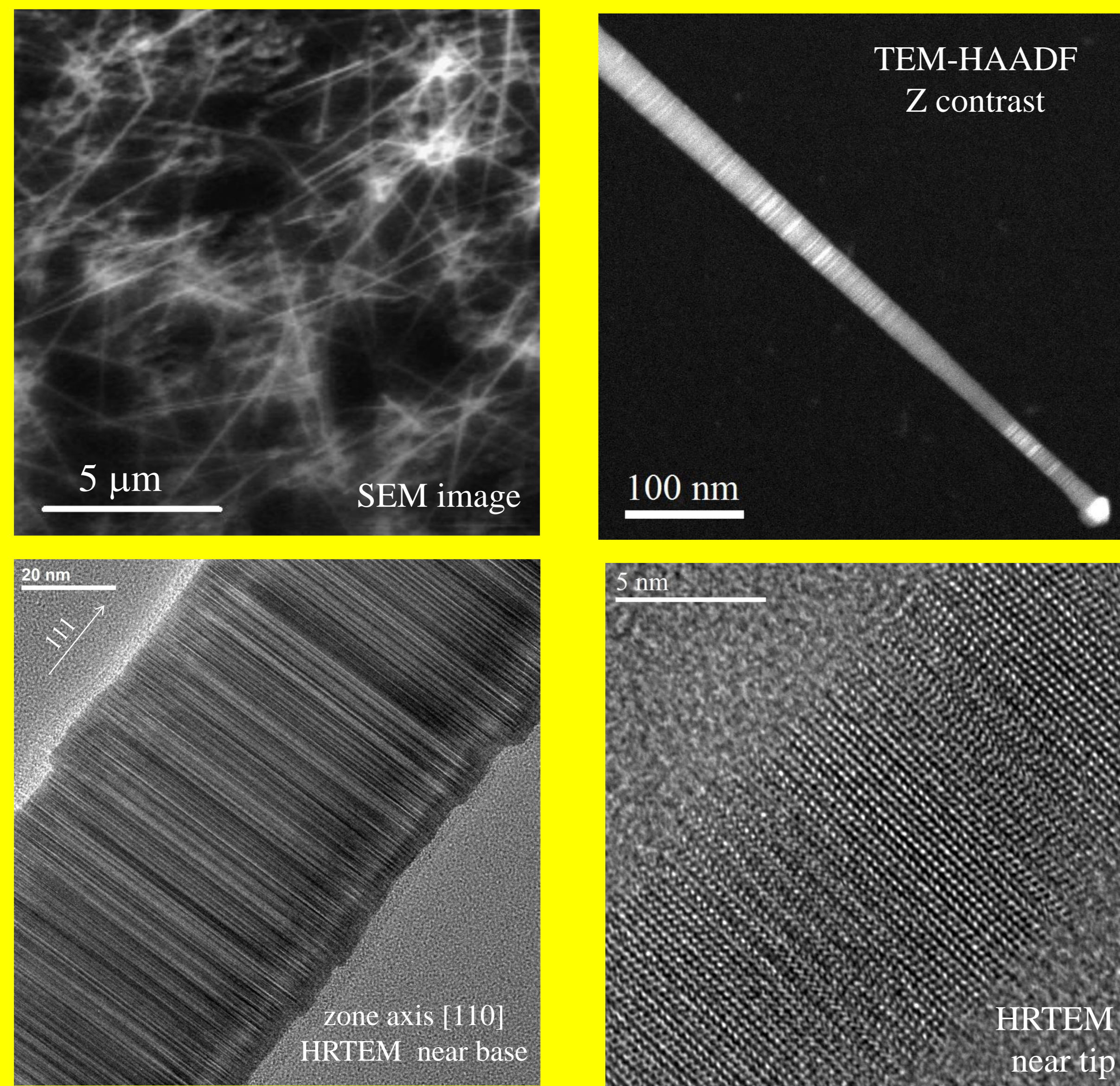
### A) Core / shell 3C-SiC/SiO<sub>2</sub> NWs \*\*

The NWs have a core-shell structure, with a  $\beta$ -SiC crystalline core ( $\leq 50$  nm) coated by an amorphous SiO<sub>2</sub> shell. The core has a 3C structure with some stacking faults and rotational twins mainly on (111) planes perpendicular to the growth axis, as common in  $\beta$ -SiC.



### B) 3C-SiC NWs grown by VPE

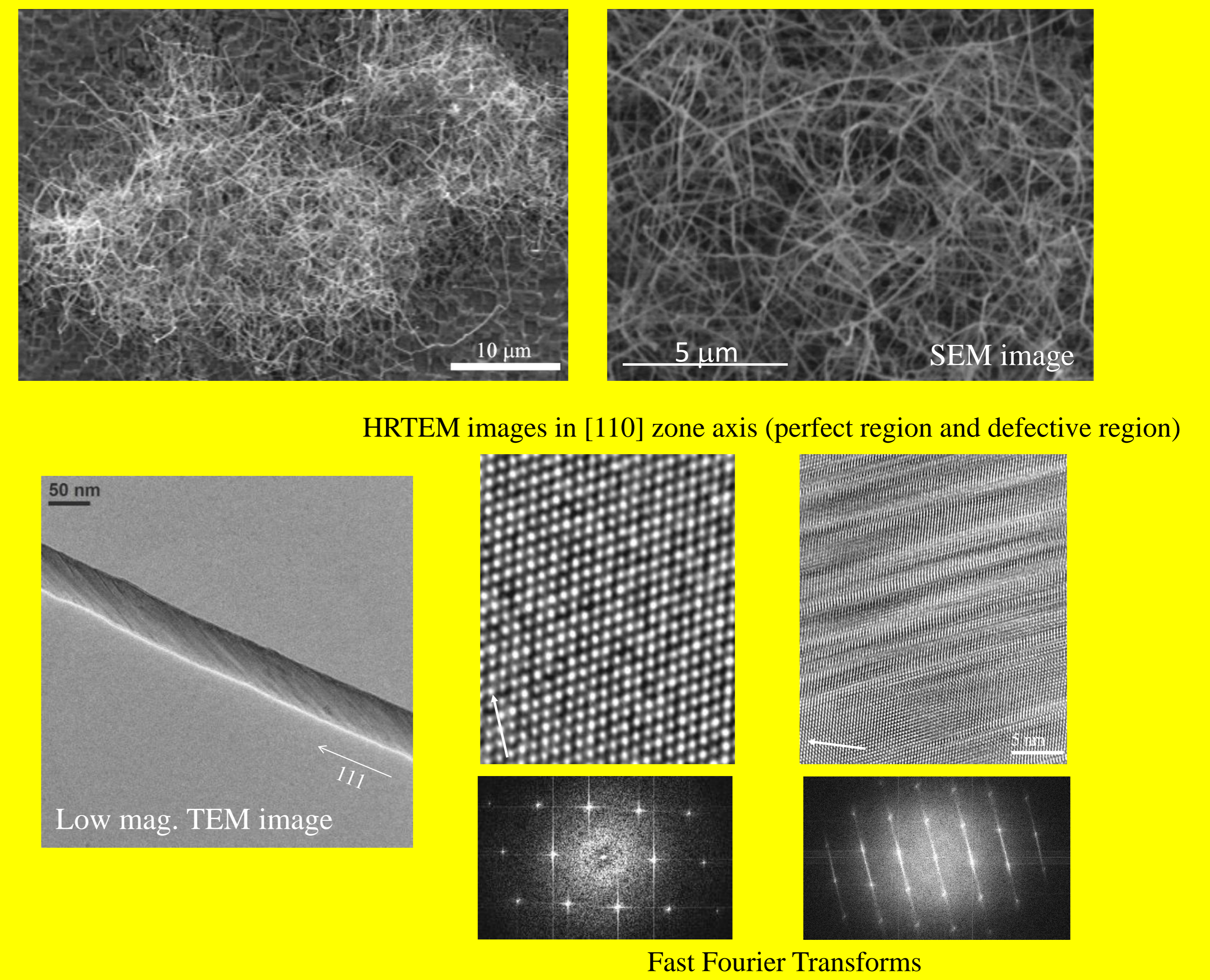
Tapered NWs are obtained: size decreases from 80 nm (base) to 10 nm (tip).



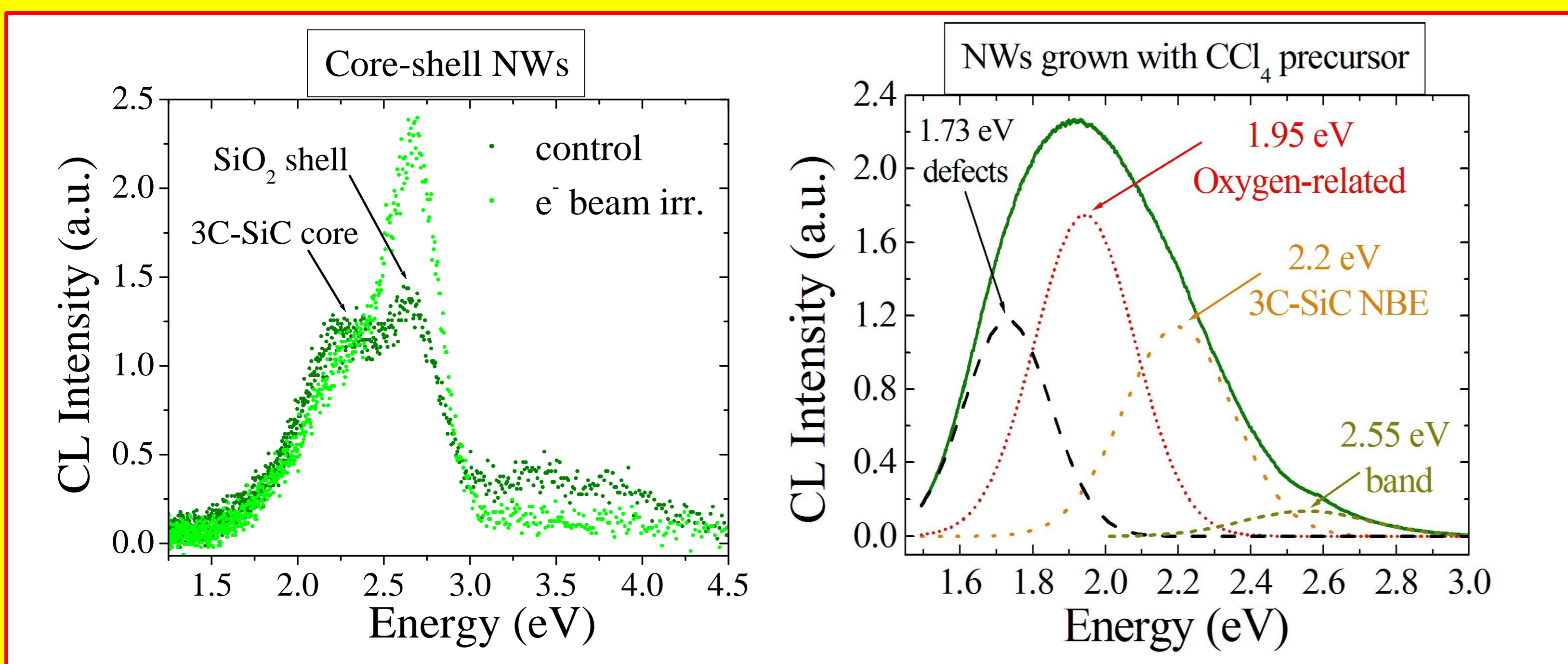
### C) 3C-SiC NWs grown with CCl<sub>4</sub> single precursor \*\*\*

Long NWs with diameters  $< 80$  nm are obtained, arranged into dense networks randomly oriented on the Si surface.

Some craters are opened in the substrate due to the etching action of chlorine.



## Optical properties: CATHODOLUMINESCENCE @ RT



In VPE-grown NWs the CL emission is too weak to be analysed. Compared to the core/shell NWs, this suggests that the shell acts as carrier injecting barrier and passivation layer, and plays a beneficial role to enhance the luminescence of the SiC core.

3C-SiC near-band-edge (NBE) transition is detected @ 2.2-2.3 eV.

Core/shell NWs show an additional blue emission @ 2.7 eV. It increases and becomes dominant under electron beam irradiation (15 keV, 2 nA, 3600 sec). Experiments performed after etching treatments confirm the attribution of this blue luminescence to oxygen deficiency centers in the amorphous SiO<sub>2</sub> shell.

In NWs grown using CCl<sub>4</sub> the spectrum is dominated by a red emission @ 1.95 eV, ascribed to O<sub>C</sub> defects unintentionally incorporated in the open-tube growth.

The other bands below and above the SiC energy gap are ascribed to deep levels in 3C-SiC with an activation energy of about 0.5 eV (emission @ 1.73 eV) and to surface states as dangling bonds or surface/interfacial groups (emission @ 2.55 eV).

## CONCLUSIONS

$\beta$ -SiC and  $\beta$ -SiC/SiO<sub>2</sub> core-shell NWs have been grown on Si substrates by:  
 A) CVD growth using CO as the carbon source,  
 B) VPE growth with silane and propane precursors,  
 C) synthesis by chemical reaction with CCl<sub>4</sub> single precursor.  
 The lattice structure and the elemental composition of the wires have been assessed by TEM. CL spectroscopy has been performed, finding a luminescence enhancement in core-shell structures due to a beneficial role of the SiO<sub>2</sub> shell layer. In NWs grown using CCl<sub>4</sub> precursor, an anomalous red luminescence centered at about 2 eV has been detected and ascribed to point defects related to an unintentional oxygen incorporation.

\*\* G. Attolini, F. Rossi, M. Bosi, B.E. Watts, and G. Salviati, J. Non-Cryst. Solids. 354, 5227 (2008);  
 F. Fabbri, A. Cavallini, G. Attolini, F. Rossi, G. Salviati, B. Dierre, N. Fukata, and T. Sekiguchi,  
 Mater. Sci. Semicond. Process. (2008) (doi:10.1016/j.mssp.2008.10.004)  
 \*\*\* G. Attolini, F. Rossi, F. Fabbri, M. Bosi, B. E. Watts, and G. Salviati, Mater. Lett. (2009)  
 (doi:10.1016/j.matlet.2009.09.012)